

44. A laser irradiation apparatus of claim 42, wherein said laser oscillator is a member selected from the group consisting of an excimer laser, a YAG laser and a glass laser.

45. A laser irradiation apparatus of claim 42, wherein said laser oscillator is a member selected from the group consisting of a YVO₄ laser, a YLF laser and an Ar laser.

46. A laser irradiation apparatus for forming a laser beam elongated in one direction on an irradiated surface, comprising:

a laser oscillator; and

two reflectors for splitting said laser beam, each including a plurality of reflective surfaces.

47. A laser irradiation apparatus of claim 46, wherein said laser beam has a length of 600 mm or more along said one direction on said irradiated surface.

48. A laser irradiation apparatus of claim 46, wherein said laser oscillator is a member selected from the group consisting of an excimer laser, a YAG laser and a glass laser.

49. A laser irradiation apparatus of claim 46, wherein said laser oscillator is a member selected from the group consisting of a YVO₄ laser, a YLF laser and an Ar laser.

50. A laser irradiation apparatus for forming a laser beam elongated in one direction on an irradiated surface, comprising:

a laser oscillator;

a first reflector for splitting said laser beam, said first reflector including a plurality of reflective surfaces; and

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a second reflector for splitting said laser beam, said second reflector including a plurality of plane mirrors.

51. A laser irradiation apparatus of claim 50, wherein said laser beam has a length of 600 mm or more along said one direction on said irradiated surface.

52. A laser irradiation apparatus of claim 50, wherein said laser oscillator is a member selected from the group consisting of an excimer laser, a YAG laser and a glass laser.

53. A laser irradiation apparatus of claim 50, wherein said laser oscillator is a member selected from the group consisting of a YVO₄ laser, a YLF laser and an Ar laser.--